

**AMENDMENTS TO THE CLAIMS**

The listing of claims below replaces all prior versions of claims in the application.

1. (Currently Amended): A method of manufacturing a semiconductor device comprising, in the recited order, the steps of:

forming an insulating film on a surface of a semiconductor element or a circuit wiring board having electrodes on the surface thereof;

forming openings in the insulating film by patterning the insulating film and then removing portions of the insulating film above the electrodes;

supplying a first metal into the openings;

heating the first metal to melt and coagulate the first metal;

supplying a second metal into the openings on the coagulated first metal;

heating the first metal and the second metal to melt and coagulate the first metal and the second metal; and

removing the insulating film.

2. (Original): A method of manufacturing a semiconductor device according to claim 1, wherein the first metal and the second metal are supplied into the openings by an electrolytic plating method or a vapor-deposition method.

3. (Original): A method of manufacturing a semiconductor device according to claim 1, wherein the first metal has a characteristic in which a volume thereof is increased when it is heated to be molten and coagulated.

4. (Original): A method of manufacturing a semiconductor device according to claim 3, wherein the first metal contains as a component thereof Bi or an alloy including Bi as a primary component.

5. (Original): A method of manufacturing a semiconductor device according to claim 4, wherein a content of Bi in the first metal is in the range from 20 to 70 wt% of the sum of the first metal and the second metal.

6. (Original): A method of manufacturing a semiconductor device according to claim 1, wherein the second metal contains as a component thereof at least one of Sn, Ag, In, Cu, Zn and Sb.

7. (Original): A method of manufacturing a semiconductor device according to claim 1, wherein the second metal is formed to such a height that it protrudes from the opening.

8. (Original): A method of manufacturing a semiconductor device according to claim 1, wherein the insulating film comprises a dry film resist.

9. (Previously Presented): A method of manufacturing a semiconductor device according to claim 1, wherein the first metal and the second metal are supplied into the openings by an electrolytic plating method.